-	20280	choline	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/28 14:31
-	3	(choline and clean$4 and damascene) and @ad<=19990716	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/28 14:32
-	29	choline and clean$4 and damascene	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/28 14:32
-	1	(choline and clean$4 and damascene) and @ad<=19980716	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/28 14:32
-	48	(choline with clean$4) and @ad<=19980716	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/28 14:32
-	10	((choline with clean$4) and @ad<=19980716) and copper	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/28 14:32
-	937	(438/618).CCLS.	USPAT; US-PGPUB	2004/07/12 13:24
-	237	((438/618).CCLS.) and clean$3	USPAT; US-PGPUB	2004/07/12 13:24
-	96	(((438/618).CCLS.) and clean$3) and low with (dielectric or insulating)	USPAT; US-PGPUB	2004/07/12 13:24
-	64	((((438/618).CCLS.) and clean$3) and low with (dielectric or insulating)) and (photoresist or "photo resist")	USPAT; US-PGPUB	2004/07/12 13:54
-	445	(438/906).CCLS.	USPAT; US-PGPUB	2004/07/12 13:55
-	168	((438/906).CCLS.) and (photoresist or "photo resist")	USPAT; US-PGPUB	2004/07/12 13:55
-	19	(((438/906).CCLS.) and (photoresist or "photo resist")) and low with (dielectric or insulating)	USPAT; US-PGPUB	2004/07/12 13:55

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